

# [HOLDER OF PHOTOMASK]

## Abstract

The present invention relates to an apparatus of holder of photomask for holding the photomask, which is placed in the transfer box and to be exposed by projecting light during process of manufacturing semiconductor, and more particularly to one being able to prevent the photomask from friction with the protrusions therein in consequence of not creating any dust particle. The holder is made of material of PEEK or VESPEL, which is abrasion resisting and high hardness. On the side of the protrusion is shaped in inclination toward center with the top in long cambered surface as supporting ridge. And, at distal end of the supporting ridge, a pedestal is given to jointly integrate with the holder so that the photomask can be placed thereon. Thus, by means of the supporting ridge with the long cambered surface of the protrusion to uphold photo mask, the contacting area of friction is reduced. Moreover, the characteristics of the protrusion is abrasion resisting and high hardness prevent from friction with the Chromium (Cr) deposition on the bottom surface of the photomask therein in consequence of not creating any dust particle.